

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
5917/FET/FET/DVSERIAL NO.
09/998,372RECEIVED
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3700 MAIL ROOMAPPLICANT
Young Joseph PAIKFILING DATE
November 30, 2001GROUP
3723

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
BS	4,698,766	10/06/87	Entwistle et al.			05/17/85
	4,967,381	10/30/90	Lane et al.			07/06/89
	5,208,765	05/04/93	Turnbull			07/20/90
	5,226,118	07/06/93	Baker et al.			01/29/91
	5,231,585	07/27/93	Kobayashi et al.			06/20/90
	5,420,796	05/30/95	Weling et al.			12/23/93
	5,469,361	11/21/95	Moyne			06/06/94
	5,525,808	06/11/96	Irie et al.			12/20/94
	5,586,039	12/17/96	Hirsch et al.			02/27/95
	5,603,707	02/18/97	Trombetta et al.			11/28/95
	5,664,987	09/09/97	Renteln			09/04/96
BS	5,812,407	09/22/98	Sato et al.			08/12/97
	5,828,778	10/27/98	Hagi et al.			06/12/96
BS	5,832,224	11/03/98	Fehskens et al.			06/14/96

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
BS	61-171147	08/01/86	Japan				X
	6-184434	07/05/94	Japan				X
	0 621 522 A2	10/26/94	Europe			X	
BS	8-50161	02/20/96	Japan				X
	8-304023	11/22/96	Japan				X

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

BS	February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." <i>IBM Technical Disclosure Bulletin</i> , pp. 4855-4859.
BS	October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." <i>IBM Technical Disclosure Bulletin</i> , pp. 2857-2860.

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02/20/04

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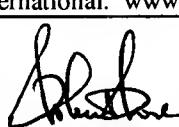
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BB	5,859,964	01/12/99	Wang et al.			10/25/96
	5,863,807	01/26/99	Jang et al.			03/15/96
	5,870,306	02/09/99	Harada			06/13/97
	5,903,455	05/11/99	Sharpe, Jr. et al.			12/12/96
	5,916,016	06/29/99	Bothra			10/23/97
	5,923,553	07/13/99	Yi			10/05/96
	5,930,138	07/27/99	Lin et al.			09/10/97
	5,940,300	08/17/99	Ozaki			05/08/97
	5,960,214	09/28/99	Sharpe, Jr. et al.			12/04/96
	5,963,881	10/05/99	Kahn et al.			10/20/97
	5,982,920	11/09/99	Tobin, Jr. et al.			01/08/97
	6,041,270	03/21/00	Steffan et al.			12/05/97
	6,078,845	06/20/00	Friedman			10/25/96
	6,112,130	06/20/00	Fukuda et al.			10/01/97
BB	6,148,246	11/14/00	Kawazome			06/10/98

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
BB	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
	11-126816	05/11/99	Japan				X

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BB	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.
BB	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp
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SA	6,175,777	01/16/01	Kim			01/16/98
	6,178,390	01/23/01	Jun			09/08/98
	6,185,324	02/06/01	Ishihara et al.			01/31/95
	6,192,291	02/20/01	Kwon			10/08/98
	6,197,604	03/06/01	Miller et al.			10/01/98
	6,211,094	04/03/01	Jun et al.			08/23/99
	6,226,792	05/01/01	Goiffon et al.			10/14/98
	6,230,069	05/01/01	Campbell et al.			06/26/98
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SA	11-135601	05/21/99	Japan				X
SA	WO 00/05759	02/03/00	WO			X	
SA	WO 00/35063	06/15/00	WO			X	

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SA	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer fabs." Semiconductor FABTECH. www.semiconductorfabtech.com/industry.news/9907/20.07.shtml
	October 15, 2001. Search Report prepared by the Austrian Patent Office for Singapore Patent Application No. 200004286-1.
	Johnson, Bob. June 10, 2002. "Advanced Process Control Key to Moore's Law." Gartner, Inc.
	July 9, 2002. International Search Report prepared by the European Patent Office for PCT/US01/24910.
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	Sonderman, Thomas. 2002. "APC as a Competitive Manufacturing Technology: AMD's Vision for 300mm." AEC/APC.

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SA	WO 00/79355 A1	12/28/00	WO	—	—	X	
SA	2001-76982	03/23/01	Japan	—	—		X
SA	WO 01/33501 A1	06/19/01	WO	—	—	X	

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